

#### **III/V Silicon QC-Lasers and Photonic Integrated Circuits: Towards Ultimate Miniaturization of Mid-IR Sensors**

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## **Chemical Sensing Requirements**

- The same principle of operation (BB source+ PA cell)
- We have two opposites:
  - 1) A testing lab solution with ultra-low detection limit

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- 2) A low cost/footprint solution with moderate performances
- Our developments on Si: 1+2 thanks to finely tuned devices / integration

Leakage

Safetw

Low-cost PA-CO2 sensor:

- Indoor air quality monitoring
  → Application: Smart IoT devices
- LoD: 400 ppm
- Footprint: <sup>1</sup>/<sub>2</sub> cm<sup>2</sup>, typically

Measure

**Size** 



Courtesy from ThermoFisher Scientific

FTIR equipment: Part of a testir

Air Quality

Limit of Detection

- Part of a testing lab solution
  - $\rightarrow$  detecting gases and chemicals < <ppm
  - $\rightarrow$  In a laboratory w/ well-controlled ambient conditions



Green House Gasses

erformances

Humidity

Ownership

## **Concept of Integrated Multigas Sensor on Si**



Array Quantum Cascade Lasers on Si

Multigas detection enabler Photonics Integrated Circuit Beam Combiner

Replace costly and fragile discrete optics Gas sensing cell – PA detector with MEMS µPhone

Replace bulky multipass cells

## Laboratory Gas measurement: Limit of Detection

 $S_{PA} \propto \frac{\alpha(C_{gas})}{\sqrt{V_c}} P_0$ 

#### Linear sensor's response : $CO_2$ ; CO; H-CHO; NO; $CH_4$ ; $NH_3$ ; $NO_2$ ...



## Mid-IR PICs – Results on MUX/DEMUX

#### SiGe/ Ge MIR-PICs



Mid-IR photonics circuit based on Si<sub>60</sub>Ge<sub>40</sub>/Si

- Wavelength range: 3µm 8µm
- Propagation loss: 0.3dB/cm (@4.5µm)
- Combiner 35 inputs with low insertion loss (-1.6 dB)
- cross talk < -12 dB</p>
- Mid-IR photonics circuit based on Ge/SiGe
  - Wavelength range:  $\rightarrow$  12µm
  - Propagation loss: 5dB/cm (@9.5µm)





# Heterogeneous integration on Silicon: a 200mm platform for large-scale and high-yield production

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#### Integration scheme developed @ Leti



- Process Flow
  - WB: wafer bonding & substrate removal
  - A: DFB definition
  - B: DFB encapsulation and ride waveguide definition
  - C/D: passivation and contact opening
  - E: Metallization / contact definition



#### 2" & 4" wafer bonding and InP substrate removal









#### DFB etching / definition (with specific EP-detection)



#### Deep ridge QCL waveguide







## **III/V Silicon QC-Lasers**

#### Results

- High yield
- C-MOS/MEMS compatible process
- Performances to be improved (issues on cladding absorption, heating, metallization...)







## Design & fabrication of a hybrid Si-III/V QCL @ 4.5µm

#### Efficient power transfer of theTM00 laser mode



### **On-Chip PA Sensors – Takeaway**

## Integration on Silicon for portable and wearable devices



Industry

Process control Emission monitoring

**Defense** Hazardous chemical detection

Healthcare Breath analyses Early diseases detection

Environment

Air quality monitoring



## Thanks for your attention!

Feel free to contact us for further discussions and/or future collaborations

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### **The Principle of Optical Detection**



## **The Principle of Optical Detection**

Direct absorption versus Photoacoustic

